

Session Title:	[WA2] Nanoscale Thin Film Deposition VII
Session Date:	November 16 (Wed.), 2022
Session Time:	13:30-14:50
Session Room:	Room A (Capri Room, 2F)
Session Chair:	Prof. Woo-Hee Kim (Hanyang Univ., Korea)

[WA2-1] 13:30-13:50

Tribological Behavior of Plasma Sulfurized Molybdenum Disulfide 2D Thin Film

Kubra Aydin (Sungkyunkwan Univ., Korea), Hae Won Yoon, Chisung Ahn (KITECH, Korea), and Taesung Kim (Sungkyunkwan Univ., Korea)

[WA2-2] 13:50-14:10

Atomic Layer Deposition of Molybdenum Carbonitride Films Using New Liquid Mo Precursor

Taeseong Kang, Byunguk Kim, Sunghoon Kim, Dowwook Lee (Hanyang Univ., Korea), Mijeong Han, Jooyong Kim (Mecaro Co., Ltd., Korea), and Hyeongtag Jeon (Hanyang Univ., Korea)

[WA2-3] 14:10-14:30

Nonvolatile Memory Characteristics Associated with Oxygen Ion Exchange in Thin Film Transistors with Indium-Zinc Oxide Channel and HfO_{2-x} Gate Oxide

J. Han, B. Jeong, and T.-S. Yoon (UNIST, Korea)

[WA2-4] 14:30-14:50

Ternary Oxide Thin Films for Multiple Patterning

Byung Chul Cho, Ju Hwan Park, Sang Joon Park, and Jin Sung Chun (Wonik IPS Co., Ltd., Korea)